

(19) World Intellectual Property
Organization
International Bureau



(43) International Publication Date
2 June 2005 (02.06.2005)

PCT

(10) International Publication Number
WO 2005/049183 A1

- (51) International Patent Classification⁷: **B01D 71/70**, 67/00
- (74) Agents: OHNO, Seiji et al.; OHNO & PARTNERS, Kasumigaseki Building 36F, 2-5, Kasumigaseki 3-chome, Chiyoda-ku, Tokyo, 1006036 (JP).
- (21) International Application Number:
PCT/JP2004/017432
- (81) Designated States (*unless otherwise indicated, for every kind of national protection available*): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (22) International Filing Date:
17 November 2004 (17.11.2004)
- (25) Filing Language: English
- (26) Publication Language: English
- (30) Priority Data:
2003-388135 18 November 2003 (18.11.2003) JP
- (84) Designated States (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).
- (71) Applicant (*for all designated States except US*): **EBARA CORPORATION** [JP/JP]; 11-1, Haneda Asahi-cho, Ohta-ku, Tokyo, 1448510 (JP).
- (72) Inventors; and
- (75) Inventors/Applicants (*for US only*): **AKIYAMA, Eiichi** [JP/JP]; c/o EBARA RESEARCH CO., LTD., 4-2-1, Hon-fujisawa, Fujisawa, Kanagawa, 2510875 (JP). **ITO, Hitoshi** [JP/JP]; c/o EBARA CORPORATION, 11-1, Haneda Asahi-cho, Ohta-ku, Tokyo, 1448510 (JP). **YOKOTA, Hiroshi** [JP/JP]; c/o EBARA CORPORATION, 11-1, Haneda Asahi-cho, Ohta-ku, Tokyo, 1448510 (JP).
- Published:
— with international search report
- For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.*

(54) Title: SULFONIC ACID GROUP-CONTAINING ORGANIC-SILICA COMPOSITE MEMBRANE AND METHOD FOR PRODUCING THEREOF

(57) Abstract: Problems of the invention are to provide an organic-silica complex-type electrolyte membranewhich is expected to show electrolyte properties such as sufficient ion conductivity to be used in an electrochemical device, to have sufficient thermal resistance and mechanical strength in accordance with applications, to contain no halogen element which exerts a large environmental load, to be capable of being produced at low cost and, further, in view of being used in the electrochemical device, to suppress swelling even when impregnated with water, alcohol, a non-protonic polar solvent, an auxiliary electrolyte solution or the like, and, accordingly, to be excellent in a joining property and adhesiveness against an electrode, a method for producing the electrolyte membrane and the electrochemical device using the electrolyte membrane. To solve the problems, a production method for an organic-silica complex membrane having a sulfonic acid group which is characterized by having the steps of obtaining a sulfonic acid derivative by allowing an alkoxysilane compound having an amino group to react with a cyclic sultone and subjecting the sulfonic acid derivative to a condensation reaction is used.



WO 2005/049183 A1